# Development of an ultra-high-transmittance, highly durable EUV pellicle using multi-layer graphene (AirMembrane Corp.)

AirMembrane

◯ Research Outline

By applying an ultra-thin multi-layer graphene film to the EUV pellicle, a core component of semiconductor lithography equipment, this proposal reduces equipment power consumption by 1-3% and reduces wafer waste due to yield loss. This will reduce power demand in all digital infrastructure, including data centers and AI accelerators, accelerating GX (Green Transformation).

| City | Year of Establishment | Founder |
|---|---|---|
| Tsukuba, Ibaraki | 2017 | Yoshinori Koga<br>Masataka Hasegawa |

| Business Area/Field | Research Period | Research Grant Amount | International collaborative technology demonstration |
|---|---|---|---|
| Materials | STS<br>2025-2027 FY | JPY 293 million | - |

| Partner VC | Latest round of Fundraising | Valuation |
|---|---|---|
| - | Pre Series A | JPY 1,000 million |

Contact Information :
tel : 029-869-6551
fax : 029-869-6552

Website : https://www.airmembrane.co.jp

As of December,2025